



Session Title:	[TE1] DTCO and Computational Lithography
Session Date:	November 21 (Tue.), 2023
Session Time:	08:30-10:20
Session Room:	Room E (Sidney Room, 2F)
Session Chair:	Dr. Ryoung-han Kim (imec, Belgium)

[TE1-1] [Invited] 08:30-09:00

EUV OPC in High High-NA Extreme Ultraviolet Lithography

Young-Chang Kim and Germain Fenger (Siemens EDA, USA)

[TE1-2] [Invited] 09:00-09:30

Memory OPC Technology Development History and Future Strategy

Sungwoo Ko, Daejin Park, Duksun Han, Jeonkyu Lee, and Kyungeun Lee (SK hynix, Korea)

[TE1-3] [Invited] 09:30-10:00

Evolution of Photolithography and Patterning Paradigms: Navigating into the DTCO and STCO Scaling Era

Ryoung-han Kim (imec, Belgium)

[TE1-4] [Invited] 10:00-10:20

Lithography Modeling with Machine Learning Techniques

Yonghwi Kwon (Synopsys, Inc., USA)